

IN THE SPECIFICATION

Please rewrite the paragraph at page 12, line 22, through page 13, line 16, as follows:

Numeral 104 denotes a surface p region of the photodiode which comprises a p-type semiconductor and numeral 105 denotes an n region to function the cathode of the photodiode which comprises an n-type semiconductor, while an embedded photodiode is formed by the presence of this surface [[P]] p region. Numeral 106 denotes an insulating film made of silicon oxide of the like and numeral [[17]] 107 denotes a reset region made of an n-type semiconductor to which a predetermined reset voltage is applied via wiring or the like, while the reset region is kept at a predetermined potential. Numeral 108 denotes a reset gate of the reset switch for resetting the floating diffusion region to a predetermined potential. ~~The n region 105 and the floating diffusion region 103 partly serves for a source and a drain region of the reset switch.~~ The floating diffusion region 103 and the reset region 107 partly serves for a source and drain region of the reset switch. The floating diffusion region 103 is connected to a gate of amplification transistor (not shown) serving for signal amplifier means and serves for the input part of the signal amplification means.